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	APPLICANT SHTEIN et al.	
	FILING DATE October 23, 2003	GROUP 1762

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	PATENT NUMBER	PATENT DATE	NAME	CLASS	SUBCLASS	FILING DATE
	5,707,745	January 13, 1998	Forrest et al.			
	6,048,630	April 11, 2000	Burrows et al.			
	6,337,102	January 8, 2002	Forrest et al.			
	6,716,656	April 6, 2004	Shtein et al.			
	6,066,357	May 23, 2000	Tang et al.			
	6,165,554	December 26, 2000	Halpern et al.			
	5,356,673	October 18, 1994	Schmitt et al.			
	5,650,197	July 22, 1997	Halpern, Bret			
	5,720,821	February 24, 1998	Halpern, Bret			
	5,759,634	June 2, 1998	Zang, Jian-Zhi			
	10/233,470	September 4, 2002	Shtein et al.			

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	EP 0 173 715	4/22/92	EP				
	WO 01/61071	8/23/01	WO				
	GB 2 336 553	10/27/99	GB				

OTHER DOCUMENTS

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	Baldo, et al., "Low pressure organic vapor phase deposition of small molecular weight organic light emitting device structures", <i>Appl. Phys. Lett.</i> 71(21), pp. 3033-3035 (24 November 1997).
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